

ABSTRACT

A method of depositing a high quality metal oxide film onto a substrate of a plasma display panel is provided. At a process for forming protective layer (8) of MgO film which is a metal oxide film, the film is formed within a range of 1×10^{-1} Pa to 1×10^{-2} Pa in a degree of vacuum in evaporation room (21) which is a deposition room, so that a depositing rate and film quality improve in forming protective layer (8). As a result, a plasma display panel which can display high quality images can be manufactured.